

**The Effect of Recombination under Short-circuit Conditions on the Determination of  
Charge Transport Properties in Nanostructured Photoelectrodes**

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**Sample preparation**

A thin compact layer of TiO<sub>2</sub> is deposited onto a transparent conducting oxide covered glass (TCO; F-doped SnO<sub>2</sub>; 8 ohms/square) by spraying 0.2 M titanium diisopropoxide bis(acetylacetonate) in isopropanol followed by heating the deposited layer at 450 C for 30 min. The TiO<sub>2</sub> nanocrystals paste (Dyesol 18NR-T) was deposited by the doctor-blade technique on the TiO<sub>2</sub> compact layer and then sintered sequentially at 325C for 5 min, 375C for 5 min, 450C for 15 min, and 500C for 15 min. The average TiO<sub>2</sub> NP film thickness was 12 μm as measured by a surface profiler. After annealing the TiO<sub>2</sub> films again at 500 C in air for 30 min and then cooling them to 80–100 C, they were immersed in a solution of acetonitrile/tert-butyl alcohol (1:1, v/v) containing 0.3 mM Z907 dye for 15 h. The semitransparent counter electrodes were prepared by spreading two drops of 5 mM H<sub>2</sub>PtCl<sub>6</sub> solution in 2-propanol onto the TCO substrates (F-doped SnO<sub>2</sub>; 15 ohms/square) and subsequently firing them at 400C for 20 min. The TiO<sub>2</sub> electrode and Pt-covered counter electrode were then sandwiched together using a 25-μm thick themoplastic (Surllyn, Dupont grade 1702). The electrolyte used in the DSSCs contained 0.6 M 1-butyl-3- methylimidazolium iodide, 0.1 M LiI, 0.05 M I<sub>2</sub>, 0.5 M 4-tert-butylpyridine, and 0.1 M guanidinium thiocyanate in acetonitrile/valeronitrile (85:15, v/v%).

## Sample Measurements

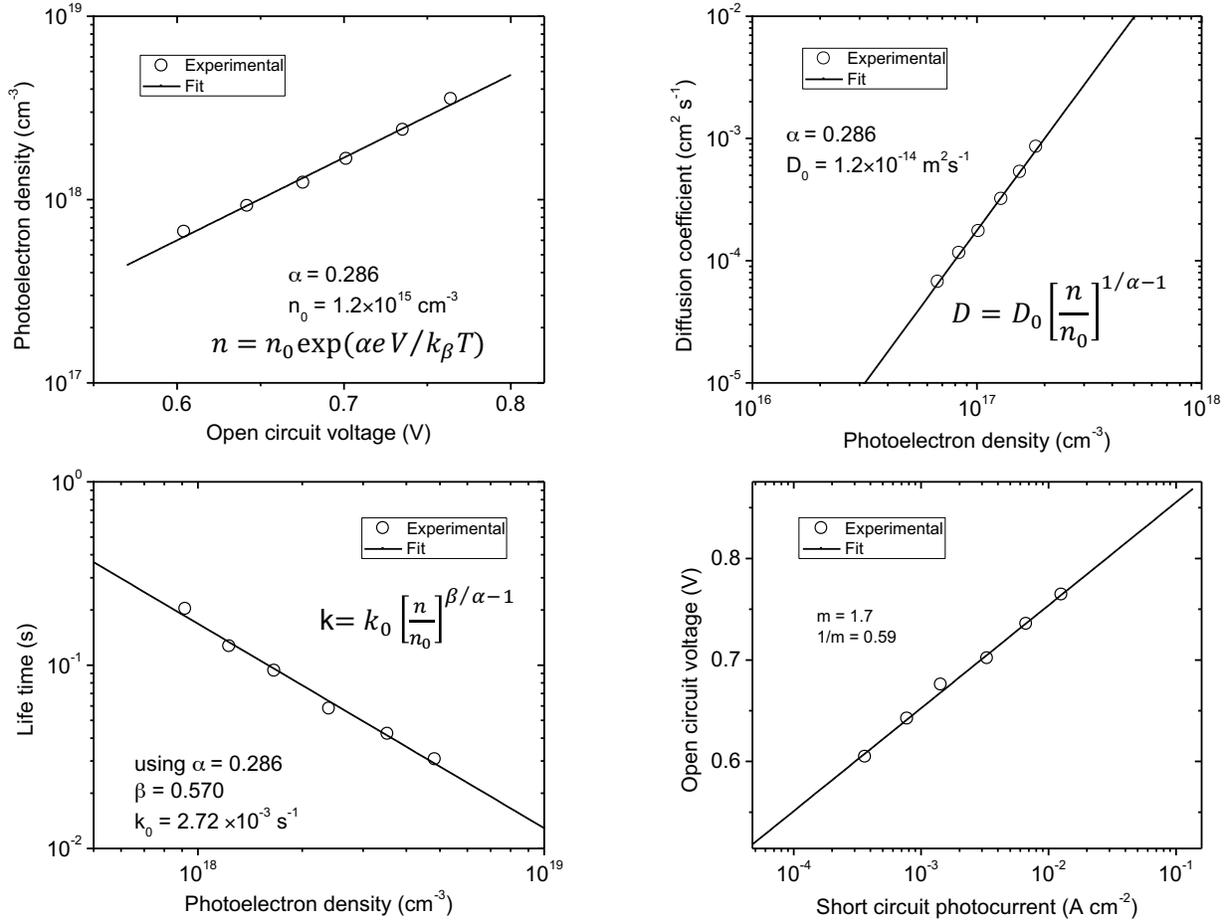


Figure S1 Parameters extraction from IMPS and IMVS measurements. Fitting equation in agreement with the total electron density model are included.

Transport and recombination were measured by intensity-modulated photocurrent spectroscopy (IMPS) and intensity-modulated photovoltage spectroscopy (IMVS).<sup>1,2</sup> The DSSCs were probed with a modulated beam of 660 nm light (probe) superimposed on a relatively large background (bias) illumination also at 660 nm light. The probe and bias light entered the cells with the TCO substrates from the TCO-TiO<sub>2</sub> side. The modulation frequencies were varied between 1 mHz and 10 kHz. Neutral density filters were used to vary the illumination intensity.

The electron diffusion coefficients  $D$  for the TiO<sub>2</sub> films were determined from the expression  $D = d^2 / (2.35\tau)$ , where  $d$  is the film thickness and  $\tau$  is the electron transport time as obtained from IMPS measurements. The steady-state photoinjected electron density  $n$  in the TiO<sub>2</sub> films was estimated from the relation  $n = T_{\alpha} J_{SC} \tau / (qd(1-P))$ ,<sup>3,4</sup> where  $T_{\alpha}$  is the thermodynamic factor,<sup>3,4</sup>  $J_{SC}$  is the short-circuit photocurrent density established by the bias light,  $P$  is the film porosity,  $q$  is the absolute value of the electron charge,  $\tau$  is the corresponding electron transport time or the life time depending whether the electron density at short circuit or open circuit is calculated. The thermodynamic factor<sup>3,4</sup> is a measure of the parameter  $\alpha^{-1} = T_0/T$ , where  $T_0$  is the characteristic temperature, which is related to the steepness of the trap distribution or the average trap depth of

the trap distribution. The current density versus voltage curve was calculated with aid of a solar simulator and potentiostat. The input parameters for the model were obtained as showed on **Figure S1**.

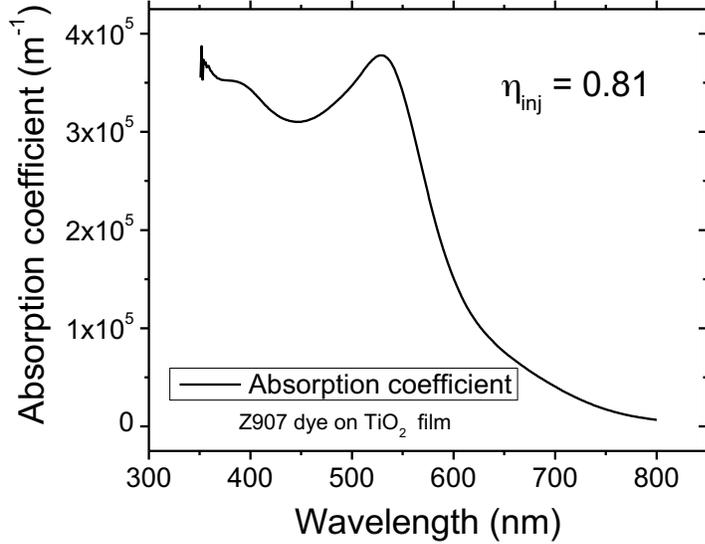


Figure S2 Absorption spectra of the sensitized TiO<sub>2</sub> film

The absorption spectra of the sensitized TiO<sub>2</sub> film was used to calculated the photo-generated charge, defined as the addition between the collected current and the recombination current. Charge injection efficiency  $\eta_{inj}$ , assumed to be constant, was used as a fitting parameter in order to fit the experimental short-circuit current density (**Figure S4**). Finally, the input parameters for the total electron density model are summarized on **Table S1**.

Table S1 Simulation parameters extracted from different measurements

Parameter	Value	Method
$\alpha$	0.286	IMPS/IMVS
$\beta$	0.570	IMVS
$n_0$ (m <sup>-3</sup> )	$1.2 \times 10^{21}$	IMVS
$D_0$ (m <sup>2</sup> s <sup>-1</sup> )	$1.2 \times 10^{-14}$	IMPS
$k_0$ (s <sup>-1</sup> )	$2.72 \times 10^{-3}$	$V_{oc}$
$\eta_{inj}$	0.810	$J_{sc}$
$d$ (m)	$12 \times 10^{-6}$	----

### Continuity equation solution for 660 nm illumination.

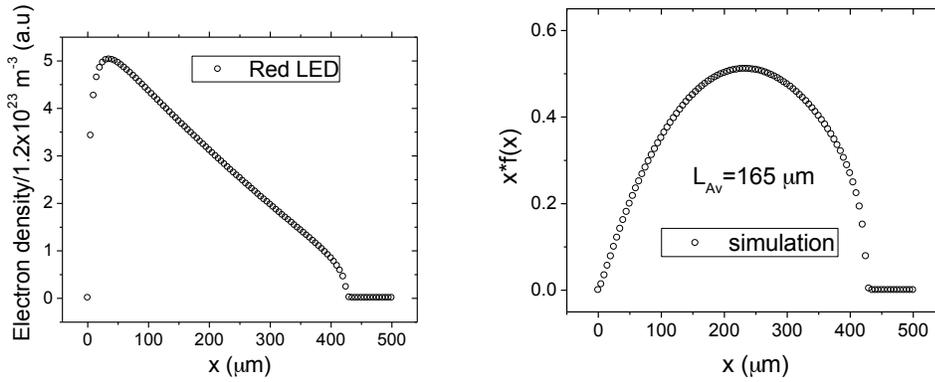


Figure S3 Electron density profile and the probability that a carrier is at position  $x$  multiplied per position as a function of charge density for Red LED illumination source

The parameters on **Table S1** were used to solve the continuity equation for the total electron density on the  $\text{TiO}_2$  electrode, **Equation 1** on the main manuscript, under real working conditions with a 660 nm LED of illumination. Method 3 was used to calculate the average diffusion length  $L_{AV} = 165 \mu\text{m}$  with the aid of **Equations 5** and **Equation 6** in the main text. SLIT simulations were performed with aid of **Table S1** to obtain the electron transport time and calculate the diffusion coefficients.<sup>5</sup>

**Figure S4** compare the experimental versus the simulated electron transport time versus short-circuit photocurrent, open circuit voltage versus short-circuit photocurrent and the current density versus voltage curves.

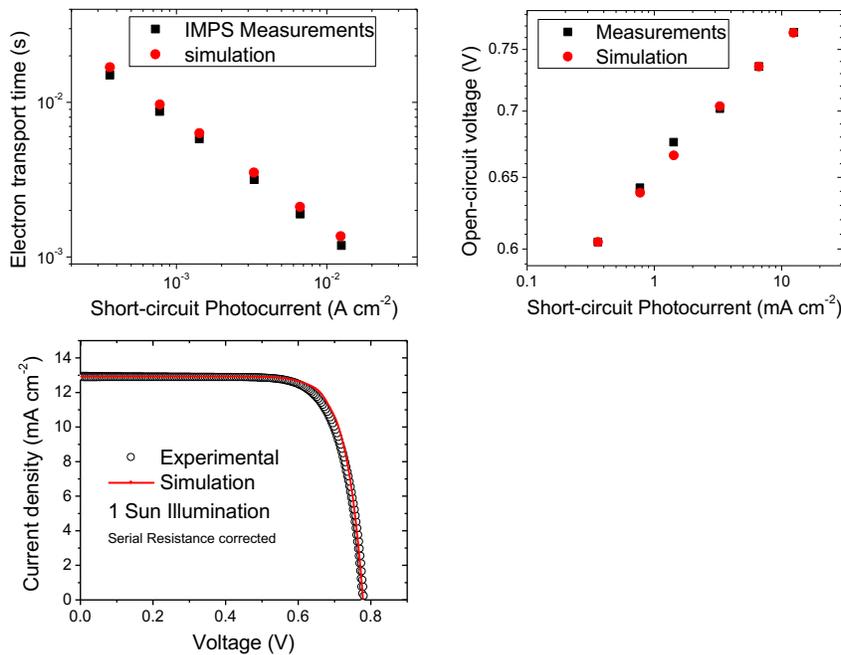


Figure S4 Comparison between experimental and simulated steady state and time dependent properties of a DSSC.

## Comparison between 660nm and Uniform illumination to obtain the real diffusion length

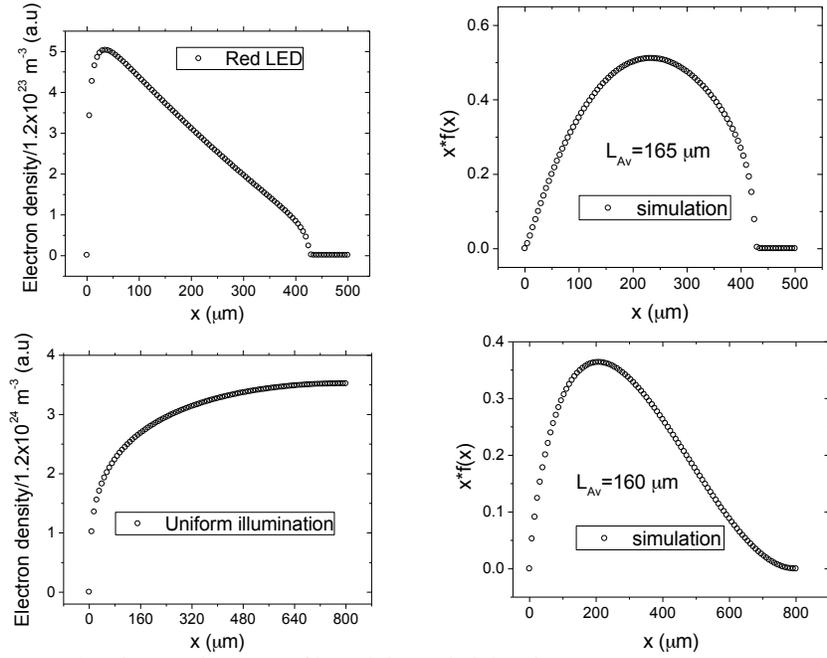


Figure S5 Electron density profile and the probability that a carrier is at position  $x$  multiplied per position as a function of charge density for Red LED and Uniform illumination sources.

The parameters on **Table S1** were used to solve the continuity equation for the total electron density on the  $\text{TiO}_2$  film, **Equation 1** on the main manuscript, under real working conditions with a 660 nm LED and uniform illumination light. Method 3 was used to calculate the average diffusion length  $\mu\text{m}$  with the aid of Equations 5 and 6 in the main text. In the case for Red illumination (660 nm) the optical length is  $\lambda=14.3 \mu\text{m}$ , as consequence when  $x$  trend to infinity the density profile goes to zero as noticed on **Figure S5**. By another side, for uniform illumination (Generation independent of position  $x$ ) the optical length is infinity and as consequence the density profile never goes to zero.

Finally, as can be notice on **Figure S5** there is not significant difference on the real diffusion length when is illuminated with red LED or with uniform light source.

## Analytical solution for the continuity equation at steady state

The continuity equation, Equation 1 on the main text, is reduced to

$$D_0 \frac{\partial^2 n(x)}{\partial x^2} + G(x) - k_0 n(x) = 0$$

For  $\alpha=\beta=1$  and at steady state, with solution:

$$n(x) = (n_0 - n_b)e^{-x/L_0} + n_b$$

where  $n_b$  is dependent of the illumination profile:

a) For exponential decay Generation

$$G(x) = I_0 e^{-\alpha_{abs} x}; \quad n_G = \frac{I_0 L_0^2}{D_0 [1 - (\alpha_{abs} L_0)^2]}$$

b) For uniform Generation

$$G(x) = I_0; \quad n_G = \frac{I_0 L_0^2}{D_0}$$

where:

- $L_0$  is the constant diffusion length,  $L_0 = (D_0/k_0)^{1/2}$
- $k_0$  is the recombination rate in dark ( $V=0$ )
- $D_0$  diffusion coefficient at  $V=0$
- $I_0$  incident photon flux ( $100 \text{ mW cm}^{-2}$ )
- $\alpha_{abs}$  is the absorption coefficient at 660 nm ( $\alpha_{abs} = 7 \times 10^4 \text{ m}^{-1}$ )

Numerical solution (Method 3) was compared with the analytical solution under the following conditions: 1) uniform illumination and 2) when  $\alpha = \beta = 1$ .

As can be notice on **Figure S6** and **Figure S7** analytical and numerical solution converge to similar value on the diffusion length.

Parameter	Value	Method
$\alpha$	1	IMPS/IMVS
$\beta$	1	IMVS
$n_0$ (m <sup>-3</sup> )	1.2x10 <sup>21</sup>	IMVS
$D_0$ (m <sup>2</sup> s <sup>-1</sup> )	1.2x10 <sup>-14</sup>	IMPS
$k_0$ (s <sup>-1</sup> )	2.72x10 <sup>-7</sup>	V <sub>OC</sub>
$n_{inj}$	0.81	J <sub>SC</sub>
$d$ (m)	12x10 <sup>-6</sup>	---

$$L_0=(D_0/k_0)^{1/2}=209 \mu\text{m}$$

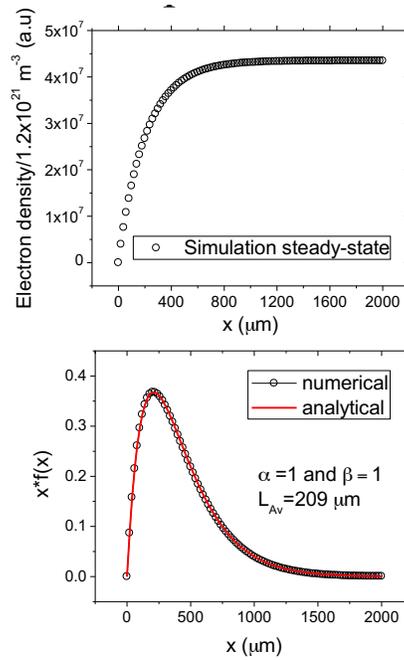


Figure S6 Numerical and Analytical solutions comparison with uniform generation profile with a constant diffusion length of 209  $\mu\text{m}$

Parameter	Value	Method
$\alpha$	1	IMPS/IMVS
$\beta$	1	IMVS
$n_0$ (m <sup>-3</sup> )	1.2x10 <sup>21</sup>	IMVS
$D_0$ (m <sup>2</sup> s <sup>-1</sup> )	1.2x10 <sup>-14</sup>	IMPS
$k_0$ (s <sup>-1</sup> )	2.72x10 <sup>-3</sup>	V <sub>OC</sub>
$n_{inj}$	0.81	J <sub>SC</sub>
$d$ (m)	12x10 <sup>-6</sup>	---

$$L_0=(D_0/k_0)^{1/2}=2.09 \mu\text{m}$$

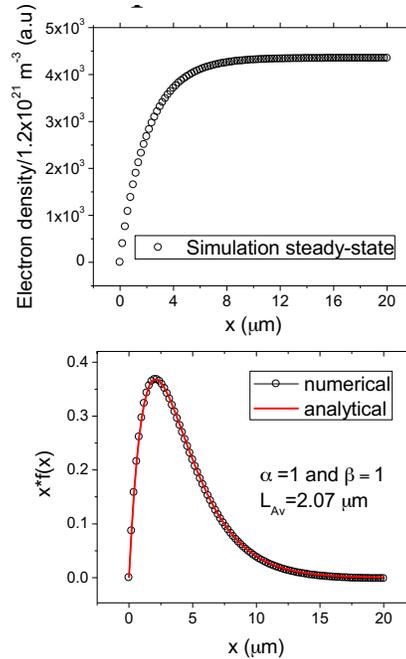


Figure S7 Numerical and Analytical solutions comparison with uniform generation profile with a constant diffusion length of 209  $\mu\text{m}$

## Geometric constant used to calculate $D$ from SLIT simulations

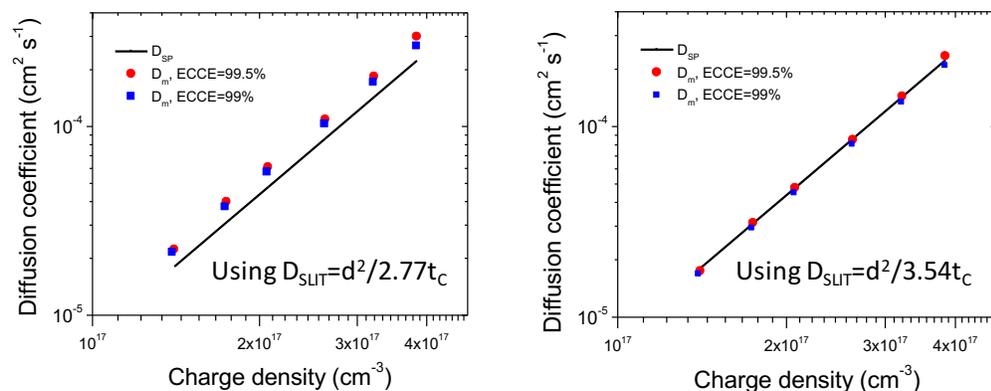


Figure S8 Geometrical constant to calculate the Diffusion coefficient from SLIT simulations

SLIT simulations were performed with aid of **Table S1** to obtain the electron transport time and calculate the diffusion coefficient<sup>5</sup> in order to compare the three methods established on the main text. As can be seen in **Figure S8**, if the factor 3.45 is used in the equation to calculate  $D_{\text{SLIT}}$  instead of 2.77, the three methods give similar diffusion coefficients.

- 1) G. Schlichthörl, S. Y. Huang, J. Sprague, and A. J. Frank. *J. Phys. Chem. B*, 1997, **101**, 8141-8155.
- 2) J. van de Lagemaat and A. J. Frank. *J. Phys. Chem. B*, 2001, **105**, 11194-11205.
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- 5) J. A. Anta, J. Idígoras, E. Guillén, J. Villanueva-Cab, H. J. Mandujano-Ramírez, G. Oskam, L. Pellejàc and E. Palomares. *Phys. Chem. Chem. Phys.*, 2012, **14**, 10285-10299.